filed 7/25/03

ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18

Stylesheet Version v18.0

Title of Invention	SYSTEM AND METHOD OF ALTERING A VERY SMALL SURFACE AREA BY MULTIPLE CHANNEL PROBE

Application Number : 10/604,486

Confirmation Number:

First Named Applicant: Hendrik Hamann

Attorney Docket Number: FIS920020170US1

Art Unit: 1765

Examiner: Alanko

Search string: (5865978 or 6002471 or 4880496 or 6078055).pn

US Patent Documents

Note: Applicant is not required to submit a paper copy of cited US Patent Documents

init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass
AKA	1	5865978	1999-02-02	Cohen		205	118
	2	6002471	1999-12-14	Quake		356	73
	3	4880496	1989-11-14	Nebenzahl, et al.		216	93
↓	4	6078055	2000-06-20	Bridger, et al.	[illegible]	250	442.2

Signature

Examiner Name	Date
Anita Alanko	6/20/05

filed 8/14/03

INFORMATION DISCLOSURE CITATION

(Use several sheets if necessary)

Docket Number (Optional)	Application Number
FIS920020170US1	10/604,486
Applicant(s)	
Hendrik F. Hamann et al.	
Filing Date	**Group Art Unit**
07/25/2003	1765

*EXAMINER INITIAL		OTHER DOCUMENTS *(Including Author, Title, Date, Pertinent Pages, Etc.)*
AHA		A Nanoplotter with Both Parallel and Serial Writing Capabilities, Seunghun Hong and Chad A. Mirkin, Science Magazine, Vol. 288, June 9, 2000) pp 1808-1811. ✓
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		AFM Single & Dual Wire Thermal & Electrochemical Glass Sensors & Heaters, Nanonics Imaging Ltd., www.nanonics.co.il August 16, 2001. ✓
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EXAMINER	DATE CONSIDERED
Anita Alanko	6/20/05

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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	Applicant(s) Hendrik F. Hamann t al.	
	Filing Date 07/25/2003	Group Art Unit

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